



TestConX 中国

China™

October 25, 2018

Raytour Venice Hotel - Shenzhen, China

Keynote

COPYRIGHT NOTICE

The presentation(s)/poster(s) in this publication comprise the Proceedings of the 2018 TestConX China workshop. The content reflects the opinion of the authors and their respective companies. They are reproduced here as they were presented at the 2018 TestConX China workshop. This version of the presentation or poster may differ from the version that was distributed in hardcopy & softcopy form at the 2018 TestConX China workshop. The inclusion of the presentations/posters in this publication does not constitute an endorsement by TestConX or the workshop's sponsors.

There is NO copyright protection claimed on the presentation/poster content by TestConX. However, each presentation/poster is the work of the authors and their respective companies: as such, it is strongly encouraged that any use reflect proper acknowledgement to the appropriate source. Any questions regarding the use of any materials presented should be directed to the author(s) or their companies.

The TestConX China logo and TestConX logo are trademarks of TestConX. All rights reserved.

www.TestConX.org

Large Panel Fan Out Technology Overview and Development

Dr. Lin Tingyu

National Center for Advanced Packaging (NCAP)



Suzhou ▪ October 23, 2018
Shenzhen ▪ October 25, 2018



Contents

- **Background Overview**
 - Personal and Company Introduction
 - Market analysis
 - Major technologies and global players
 - Patent aspects & distribution
 - Main process technologies
 - Challenges & solutions
 - China OSATs on fan out executions
- **Some Works Updates of Wafer Level and Panel Level Fan out in NCAP**
- **Basic Works Introduction in NCAP Consortium**
- **Critical Works Implementation in GD Province**
- **Conclusions**



Large Panel Fanout Technology Overview and Development

2018

4

Personal Introduction

More than 25-year experiences in design, process, assembly, reliability and business management in electronics IC packaging, semiconductor, consumer electronics, mobile phone assembly, PCBA, thermal and aerospace industry. Motorola certified Six Sigma Black Belt. Holding position of board member of CSR (chip scale review), have filed more than 40 international patents and 150 international Journal and conference papers; working in NCAP 5 years, and prepare to move Guangdong province for LPFO integrated equipment and process development and commercialization



NCAP Introduction

Wuxi Headquarters



- 3000m² Cleanroom
- Class 10/100/1,000/10,000
- 8"/12" wafer

Beijing Center



- 1000m² Cleanroom
- Class 1,000/10,000

- R&D & Engineering with 9000m²
- engineering assembly & metrology equipment with ¥160 million, fixed total equipment value ¥345 million.



- Established in Wuxi in 2012
- 10 investors
Including the Institute of Microelectronics and the largest OSATs and substrate companies in China (JCAP, NT Fujitsu, WLCSP, ANJILI, WULIWANG, SCC, NDB, IME, Hua Tian, XIN Sheng Kuai Jie)
- Independent business entity



Large Panel Fanout Technology Overview and Development

2018

6

CNC Equipment Innovation Institute Introduction

Foshan Nanhai Guangdong Technology University CNC Equipment Cooperation Innovation Institute is jointly set up by Guangdong Provincial Department of Science and Technology, The People's Government of Foshan Municipality, Nanhai People's Government of Foshan and Guangdong University of Technology.

Honor and Qualifications

- National High-tech Business Incubator
- National Group Innovation Space
- New R&D institution in Guangdong
- Joint-postgraduates Demonstration Base
- College Students Practical Teaching Base in Guangdong



Leadership Concern



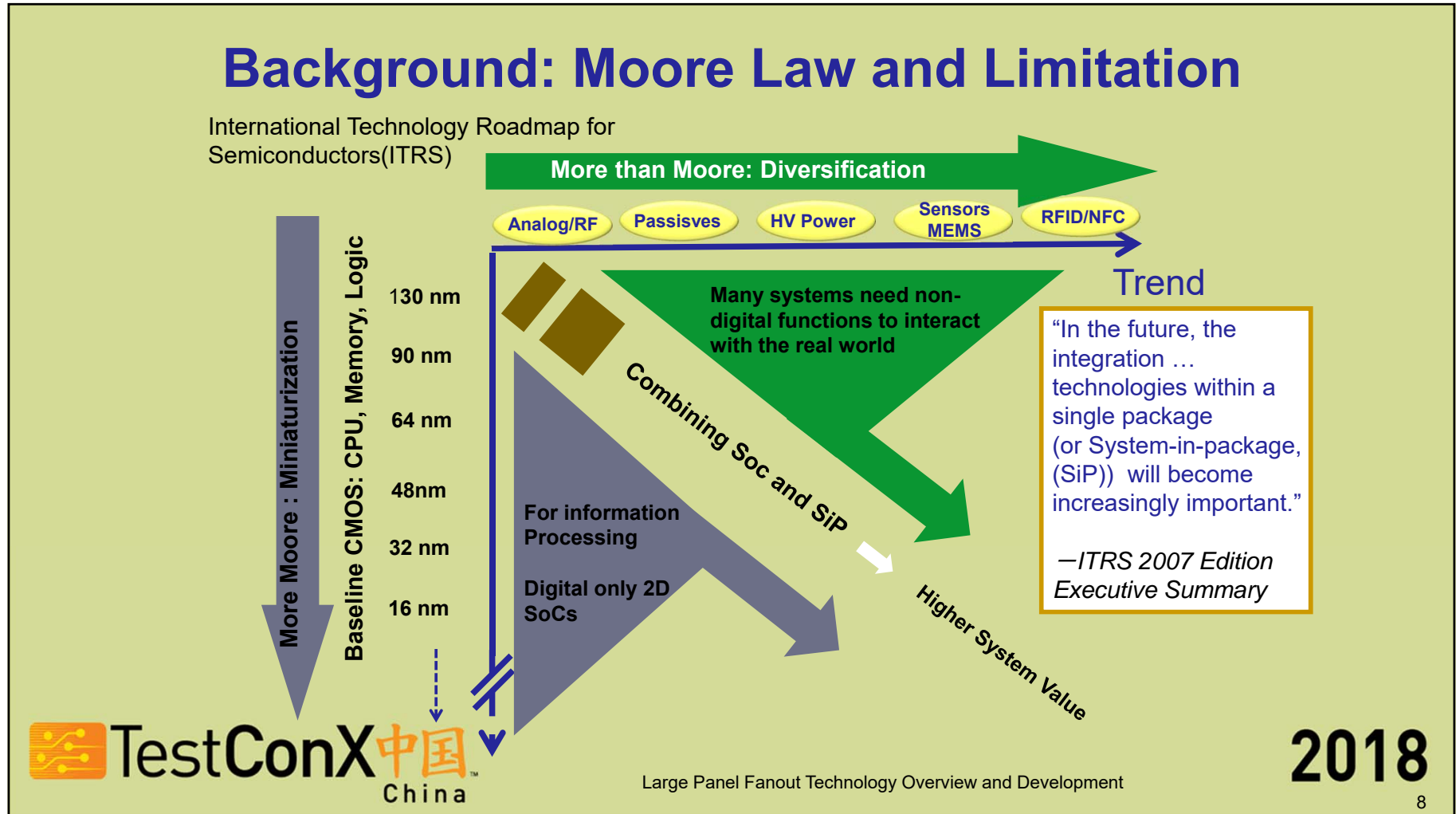
Chinese Premier Li Keqiang
inspect our work



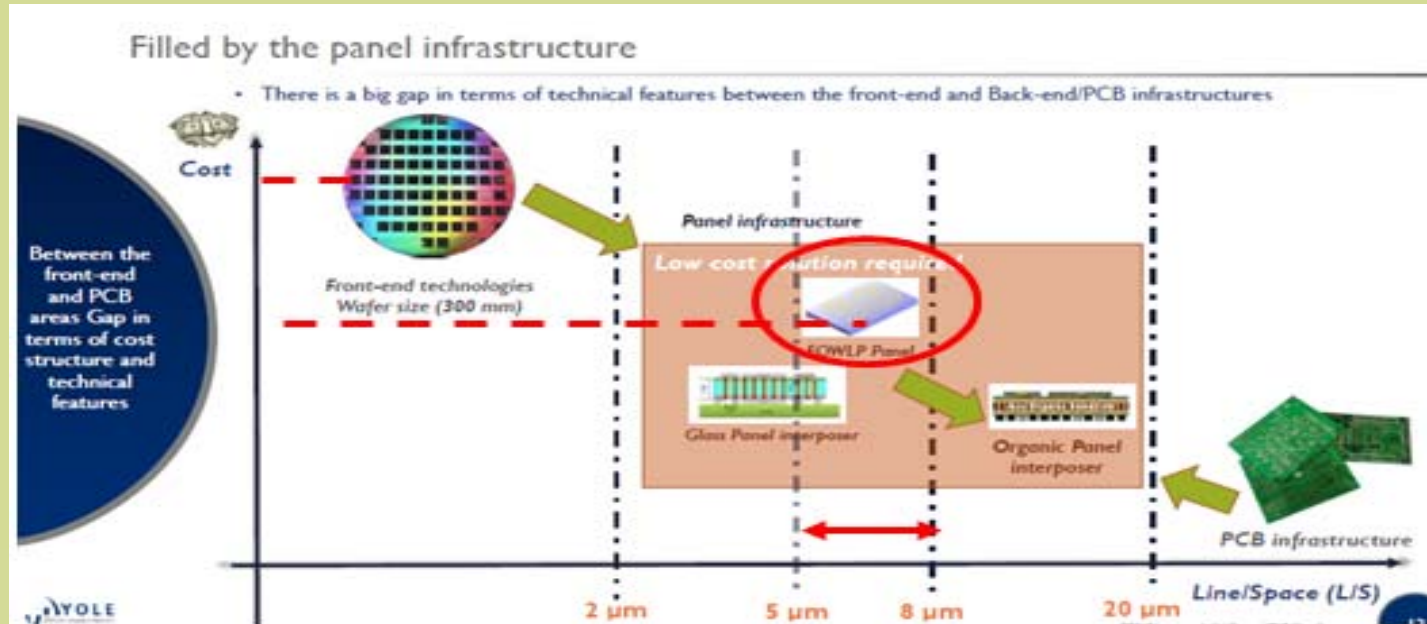
Large Panel Fanout Technology Overview and Development

2018

7



Background: Development Trend



- The extension of Moore's law is subjected to multiple pressures such as physical limits, huge investment and so on.
- The urgent need to develop a new style technology progress "More Than Moore"

Background: Why Fanout ?

Performance

- ✓ Shorter interconnect length, high speed application;
- ✓ Superior package level reliability,
- ✓ Excellent board level reliability

Cost Advantage

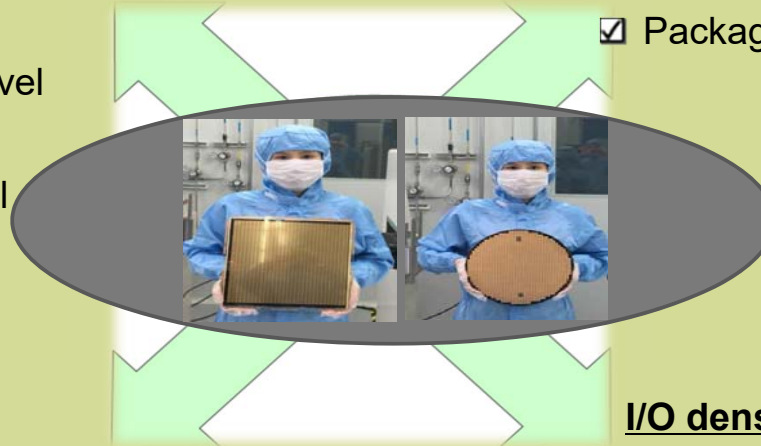
- ✓ Substrate /gold free,
- ✓ Scalable to the large panel (600mm above)

Form Factor

- ✓ Thinner package,
- ✓ Package size Scalability

I/O density

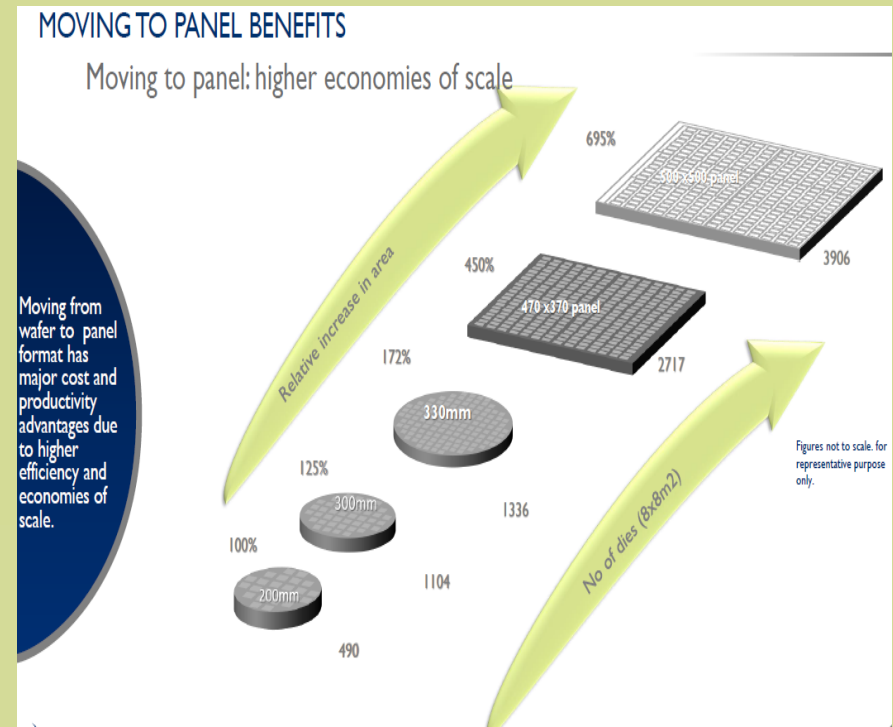
- ✓ Small pitch,
- ✓ High pin counts



Background: Advantages of LPFO

Through LPFO integration advanced packaging technology, to achieve high-density integration, volume miniaturization and lower cost.

- **The advantages of LPFO**
 - Higher integration and wider application;
 - More flexible design and higher density wiring;
 - Better electro-thermal performance, smaller and thinner volume;
 - High efficiency and low cost

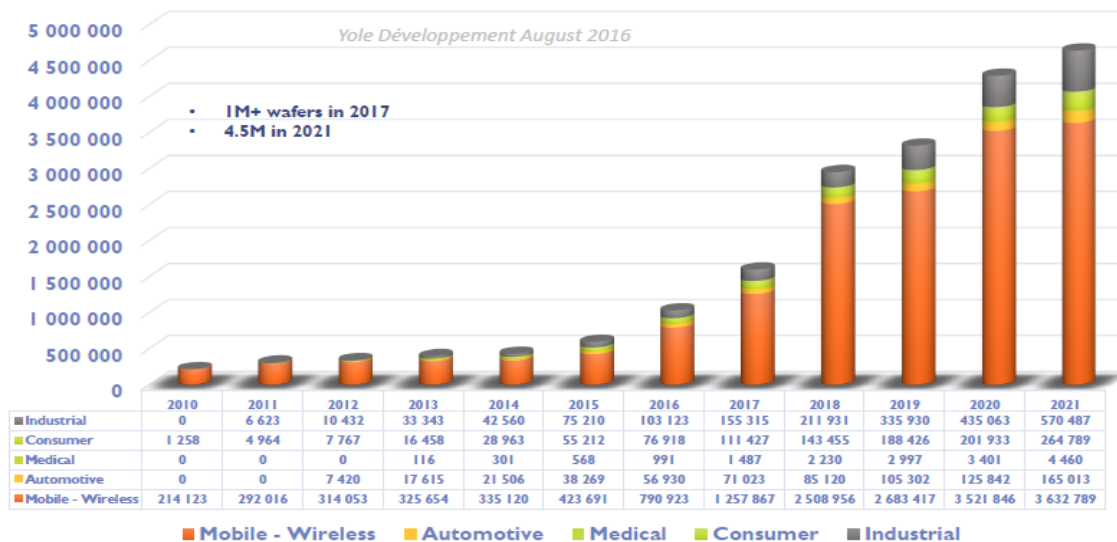


Background: Fanout Market Forecast

FAN-OUT ACTIVITY - MARKET FORECAST

Executive Summary

Fan-out activity forecast (300mm eq wafers) breakdown per end-market



Apple's example will show competitors the way



©2017 | www.yole.fr | Equipment and Materials for Fan-Out Packaging | Report

19



Large Panel Fanout Technology Overview and Development

2018

12

Background: Fanout Applications

FAN-OUT APPLICATIONS

Where do we find fan-out? Some examples below

Executive Summary

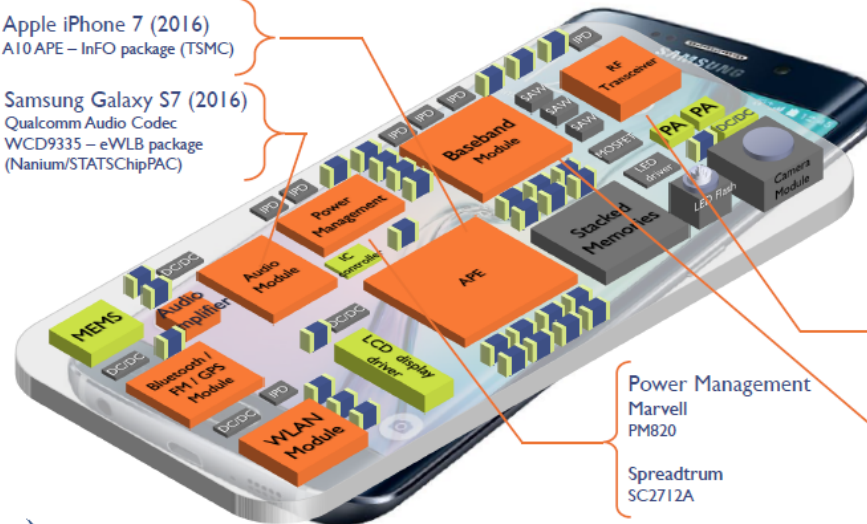
Orange: devices found in FOWLP packages today

Green: future devices that could be found in FOWLP

Grey: devices that will likely remain on WLCSP or flip-chip package, or move to 3DIC or embedded die

Apple iPhone 7 (2016)
A10 APE – InFO package (TSMC)

Samsung Galaxy S7 (2016)
Qualcomm Audio Codec
WCD9335 – eWLB package
(Nanium/STATSChipPAC)



Bosch MRR IPlus Radar (2015)
Infineon RASIC™ (77GHz RADAR System IC Chipset) – eWLB package
Continental ARS400 Radar (2015)
NXP MR2001 (77GHz multichannel RADAR) – RCP Package



BK Ultrasound Sonic Window (2015)
Multichip Module – eWLB Package (Nanium)

RF
Spreadtrum
SC8502

Intel-Mobile/Infineon
PMB5712, PMB5726

Baseband
Spreadtrum
SC8502

Intel-Mobile/Infineon
PMB7900, PMB9810, PMB9801

Power Management
Marvell
PM820

Spreadtrum
SC2712A

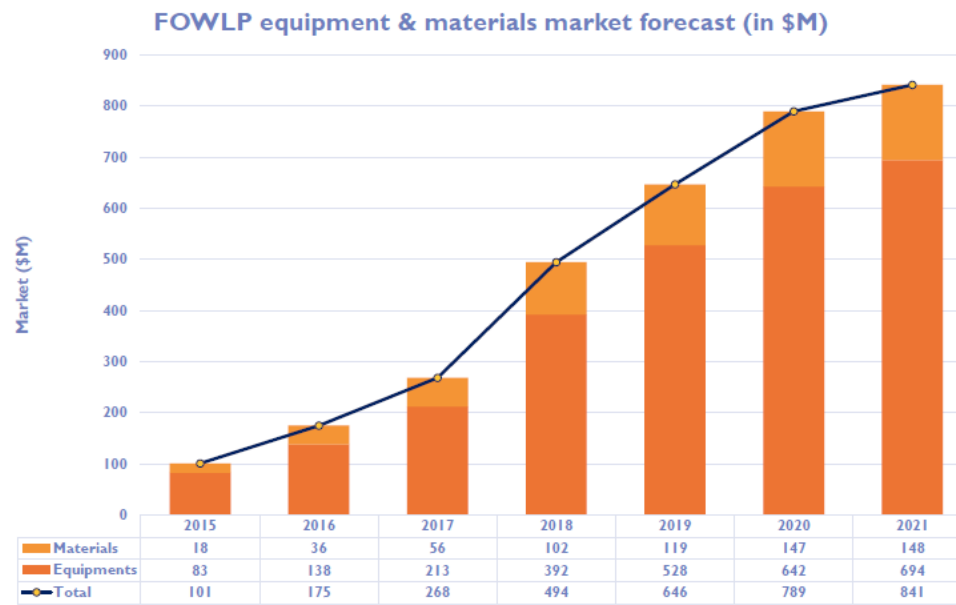


©2017 | www.yole.fr | Equipment and Materials for Fan-Out Packaging | Report

20

Background: Fanout Materials and Equipments

FOWL* - TOTAL MARKET FORECAST FOR EQUIPMENT AND MATERIALS



Executive Summary



* The market estimated here only includes process steps investigated by Yole for this report, and is not exhaustive. For details, see the following slides for breakdowns, along with the "fan-out process steps to focus on" slides in the "Challenges" section.

©2017 | www.yole.fr | Equipment and Materials for Fan-Out Packaging | Report

26



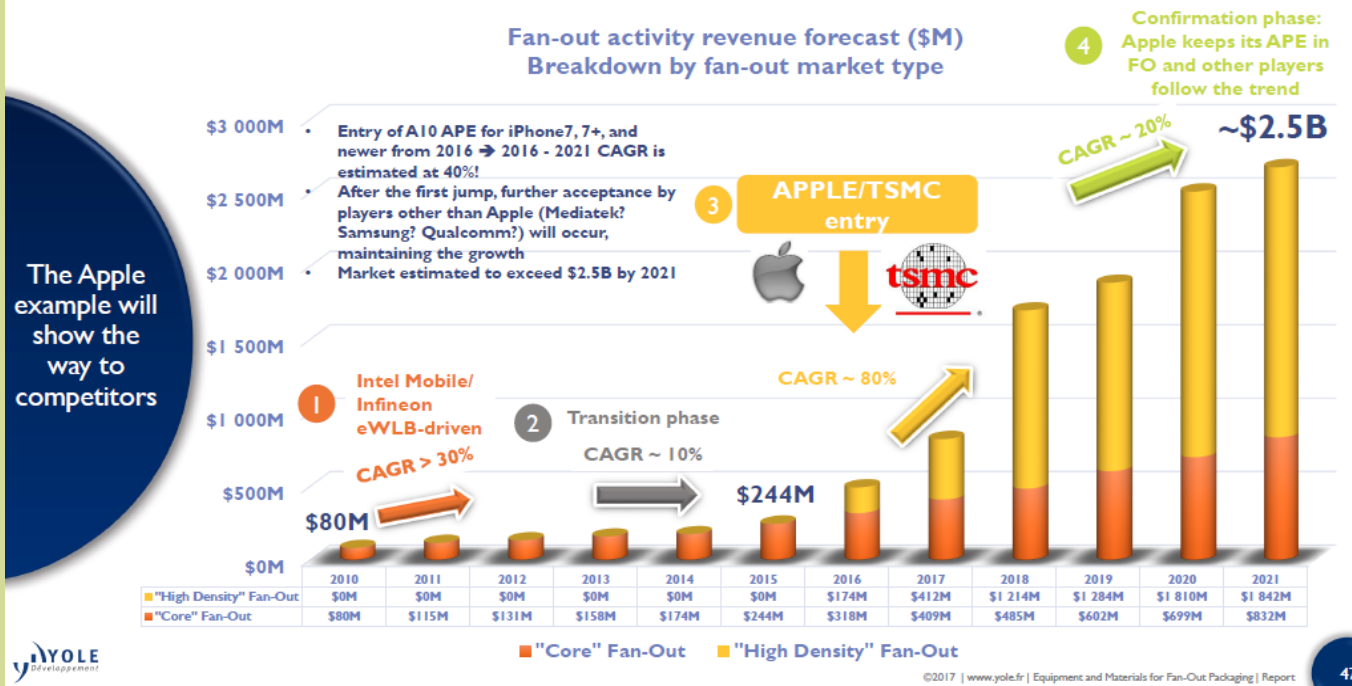
Large Panel Fanout Technology Overview and Development

2018

14




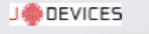




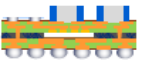




































Background: Fanout Market Driver

FAN-OUT ACTIVITY - MARKET FORECAST (1/2)



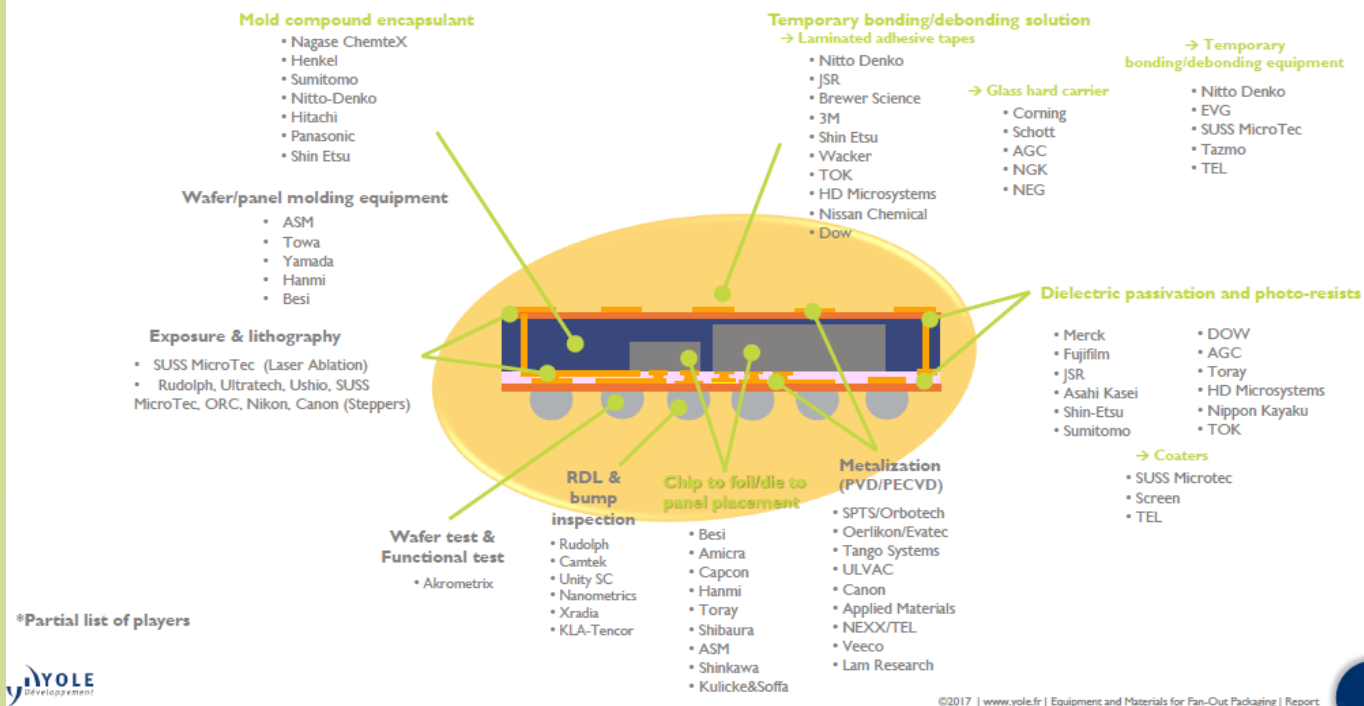
Background: Fanout Market Players

Key players pushing the panel manufacturing platform

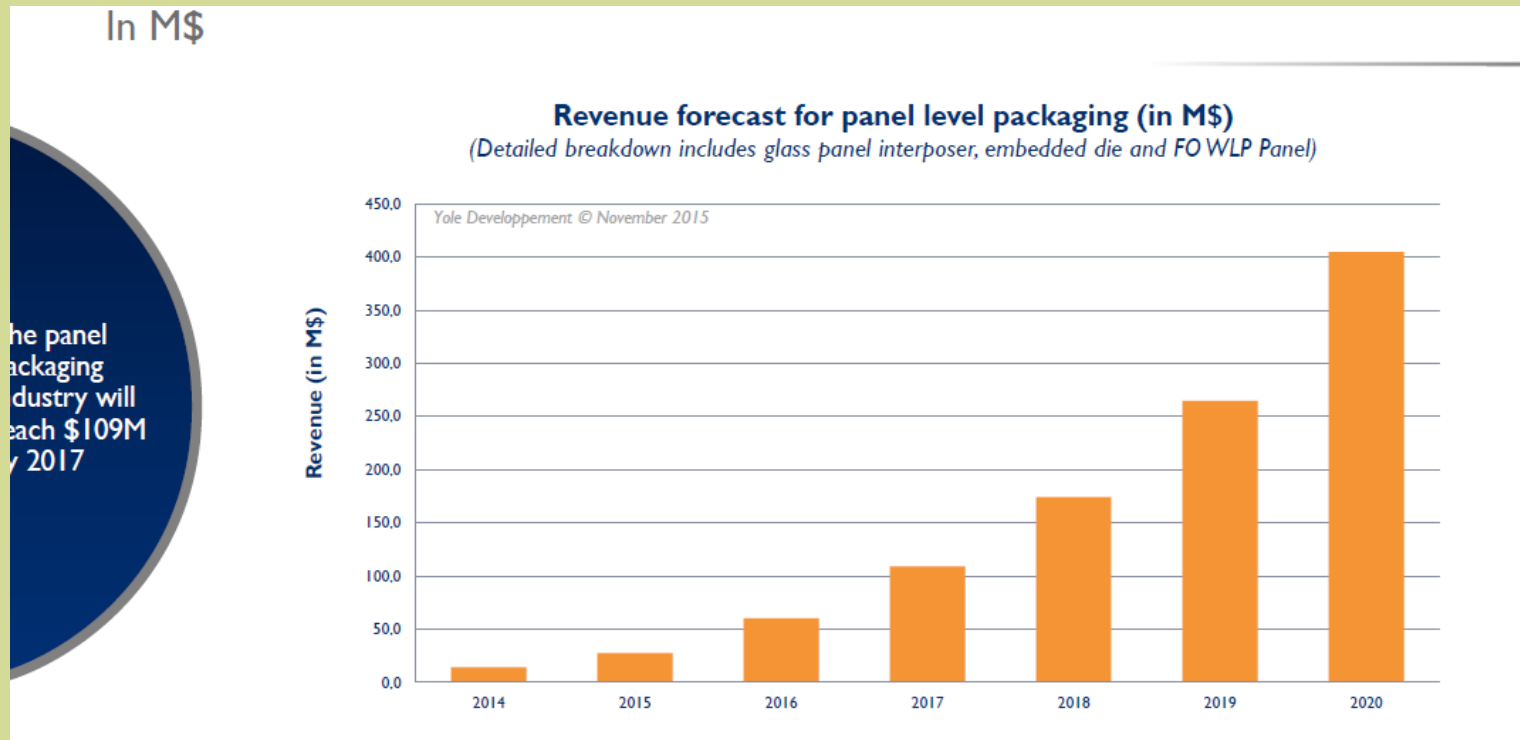
		Fabless	OSATs	Substrate makers	IDMs
FOWLP on panel		 	    		
Embedded die			 	         	
Glass interposer				    	
Organic interposer			 	   	
Hybrid interposer		  		 	

Background: Fanout Supply Chain

SPECIFIC EQUIPMENT & MATERIALS FOR FAN-OUT MANUFACTURING*



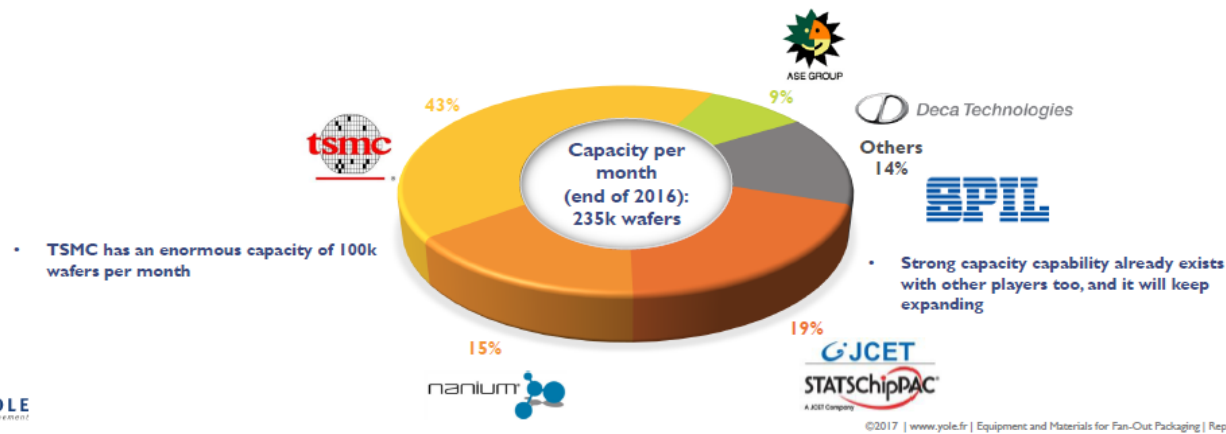
Background: Revenue from PLP



Background: Fanout Market Capacity

FOWLP - ALREADY-INSTALLED CAPACITY

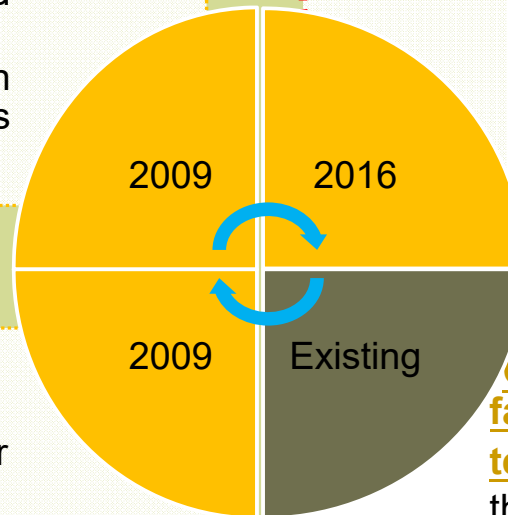
- At the end of 2016, fan-out investments were already very important, and consequently so is capacity
 - With a capacity of 100,000 wafers/month, TSMC's InFO product has the largest capacity
 - Other main manufacturers are established eVVLB providers: Nanium and STATS ChipPAC. Each can produce around 10,000 wafers per week.
 - STATSChipPAC is enlarging its capacity to raise production
 - Since TSMC's action was quite formidable, investment in equipment for 2017 will not be as high - but it will still be decent:
 - Led by newcomers willing to have a FOWLP offer
 - As well as major players willing to enlarge their capacity (STATSChipPAC and potentially ASE together with Deca)
- With 4.5M wafers to be produced in 2021, capacity must be increased by TSMC and/or other actors. Therefore, a second wave of investment will occur later on; otherwise, capacity be insufficient for addressing the FOWLP market if it keeps growing (see the following slides).



Major Fanout Technologies

- **eWLB (wafer level)**
- First fanout patent filed at 2001
- Shipped out 1 billion units since mass production in 2009


- **RCP** technology (wafer level), from frees, and licensed NEPES,
- Low volume shipment



- **TSMC InFO (wafer level)**: Apple used this technology in iPhone 7 (A10 processor)

Others (e.g., DECA (chip face up panel level) technology; ASE licensed this technology (panel level, and ship out 100 million units)

Major Fanout IPs



US006727576B2

(12) **United States Patent**
Hedler et al.

(10) **Patent No.:** US 6,727,576 B2
(45) **Date of Patent:** Apr. 27, 2004

(54) **TRANSFER WAFER LEVEL PACKAGING**

(75) **Inventors:** Harry Hedler, Germering (DE);
Thorsten Meyer, Erlangen (DE);
Barbara Vasquez, Munich (DE)

(73) **Assignee:** Infineon Technologies AG, Munich (DE)

(*) **Notice:** Subject to any disclaimer, the term of this patent is extended or adjusted under 35 U.S.C. 154(b) by 0 days.

(21) **Appl. No.:** 10/044,000
(22) **Filed:** Oct. 31, 2001

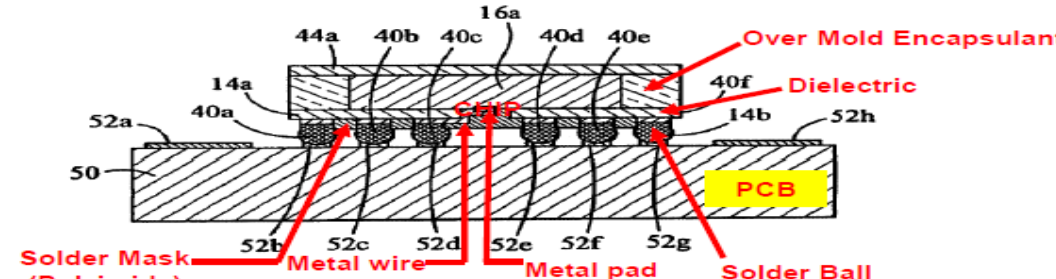
(56) **References Cited**

U.S. PATENT DOCUMENTS
6,537,848 B2 * 3/2003 Comenforte et al. 438/406
* cited by examiner

Primary Examiner—David Nelms
Assistant Examiner—Mai-Huong Tran
(74) *Attorney, Agent, or Firm*—Fish & Richardson

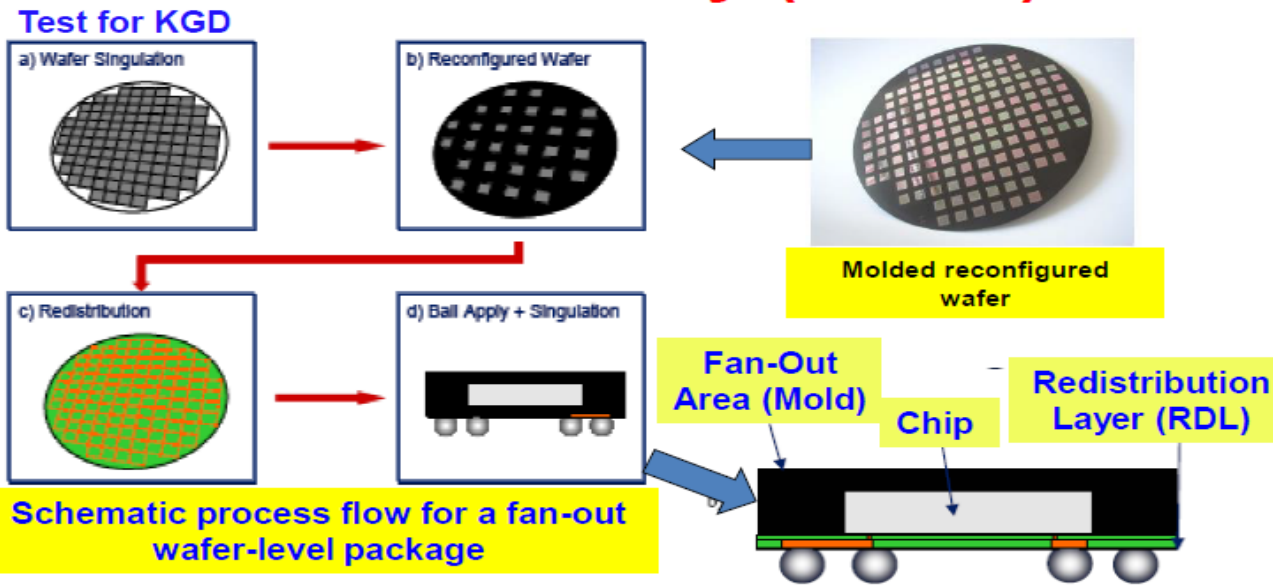
(57) **ABSTRACT**

A semiconductor structure and a method for forming the semiconductor structure, including a semiconductor chip and a conductive layer disposed over a portion of the chip.



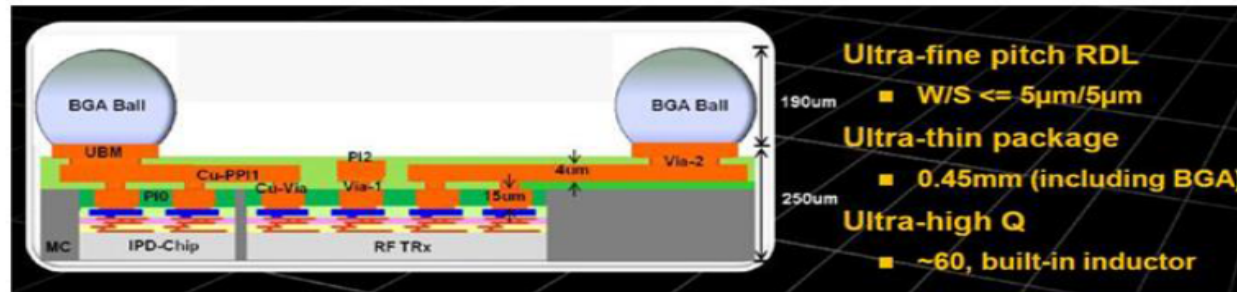
Typical eWLB Process Characterization

Infineon's Embedded Wafer-Level Ball Grid Array (eWLB)



Typical InFO-WLP Process Characterization

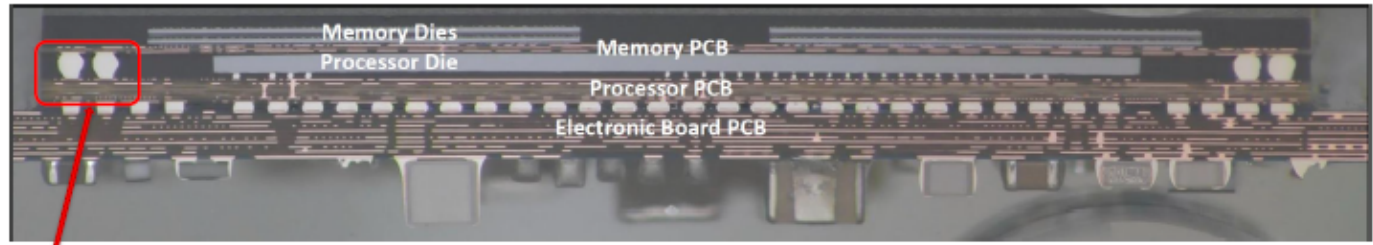
TSMC InFO-WLP (Integrated Fan-Out WLP)



At the TSMC Technology Symposium in San Jose, CA in April 2014, TSMC announced the latest InFO-WLP platforms:

- 8mm x 8mm is targeted at RF and WiFi chips
- 15mm x 15mm is targeted at application processor and baseband chips
- 25mm x 25mm could be applied to GPU and networking chips

Typical InFO-PoP



3D Interconnect for PoP

Samsung Exynos 8 in typical PoP structure
(flip chip on laminate, laser drilled via with solder fill)

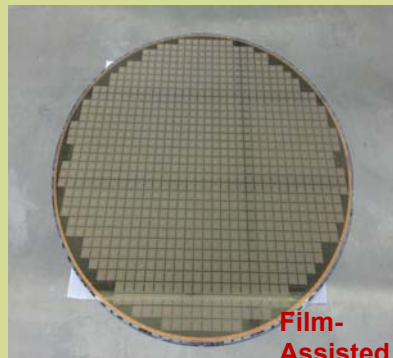


Apple A10 (iPhone 7) in TSMC InFO PoP
(chips first fan-out with ECD Cu posts)

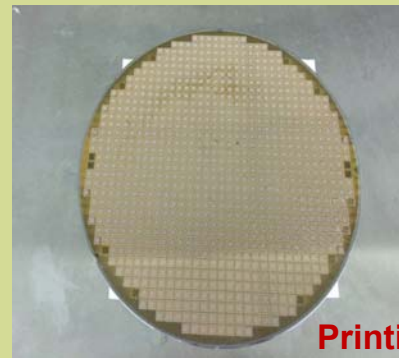
OSAT Distribution for Fan out

OSAT in China	Packaging Fan out Technologies available	status
Hua Tian Scientific Co., Ltd	eSIFO™	Qualified and engineering samples are ready; and ready for ramping in the production
JCET	MIS technology based	Ready for mass production
NT Fujitsu	Panel level fan out	In development
National Centre for Advanced Packaging (China), mass production OSAT	eWLP, PLP, etc.	Factory built up in Jiangsu province

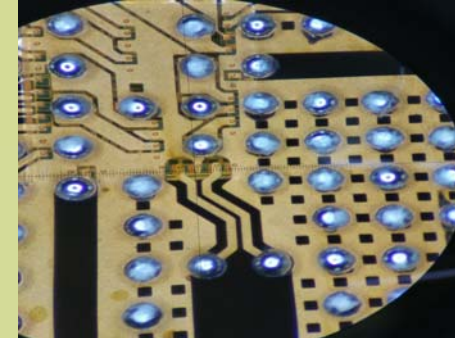
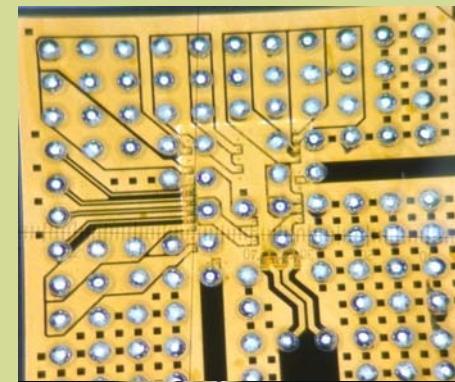
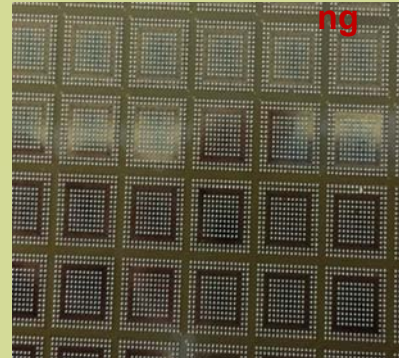
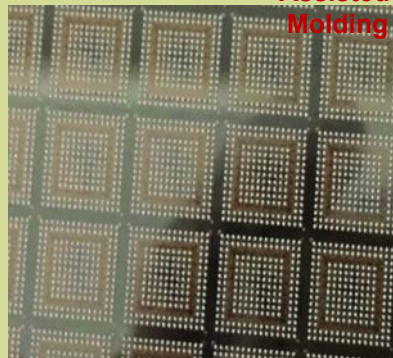
Typical NCAP eWLB Samples



Film-Assisted Molding



Printing



77G eWLB sample

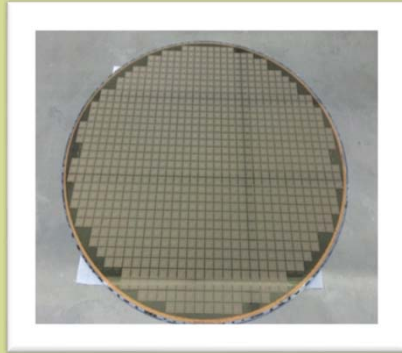


Large Panel Fanout Technology Overview and Development

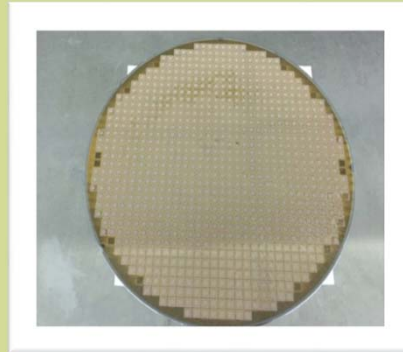
2018

26

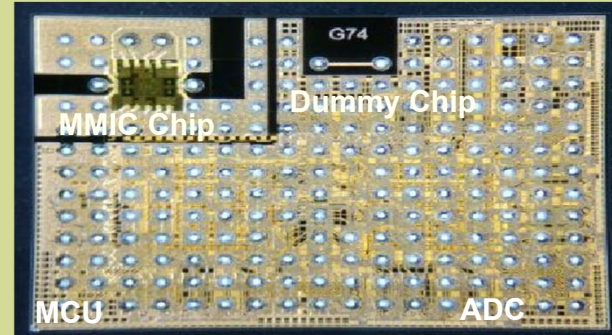
Typical NCAP eWLB Samples



Film-assisted molding



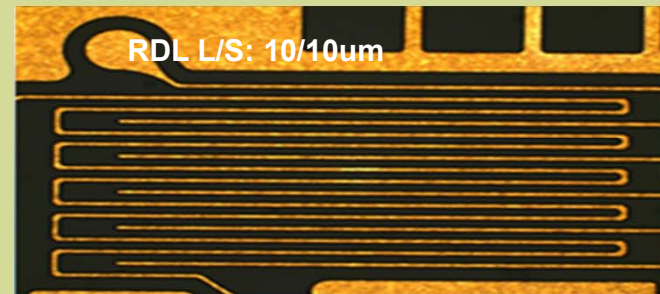
Printing



WLFO-12"



PLFO-320mmx320mm



4-chip SiP module with 204 solder balls

Key Observations from Reliability & FA

1. During reliability test, we found solder ball drop off and big voids are observed after HTS-1008 hrs and TC-750 cycles, it is confirmed that reflow profile needs to be optimized.
2. After pre-conditioning. There are delamination found between PI materials, it is confirmed process of PI curing needs to be optimized.
3. For TC test, it is found that delamination occurred between PI and die, process and material are needed to be evaluated and optimized.
4. For uHAST-144h, it is found that delamination happened between UBM and solder ball, plating and reflow process must be evaluated and optimized.

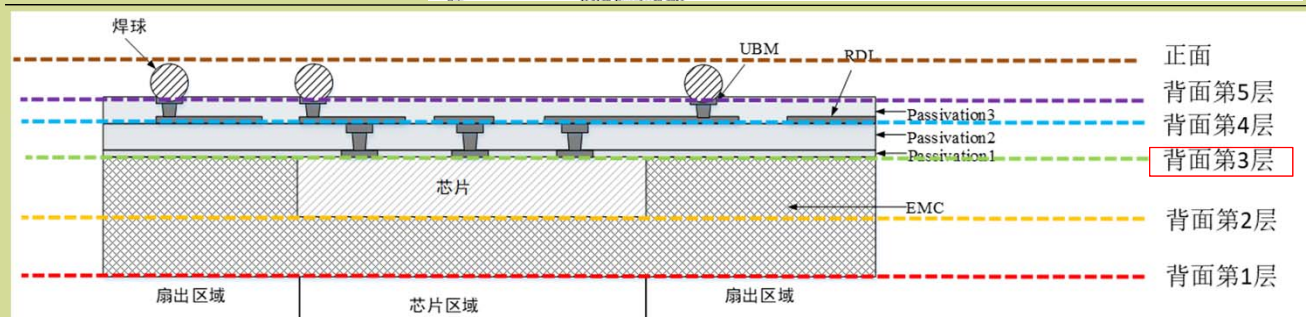
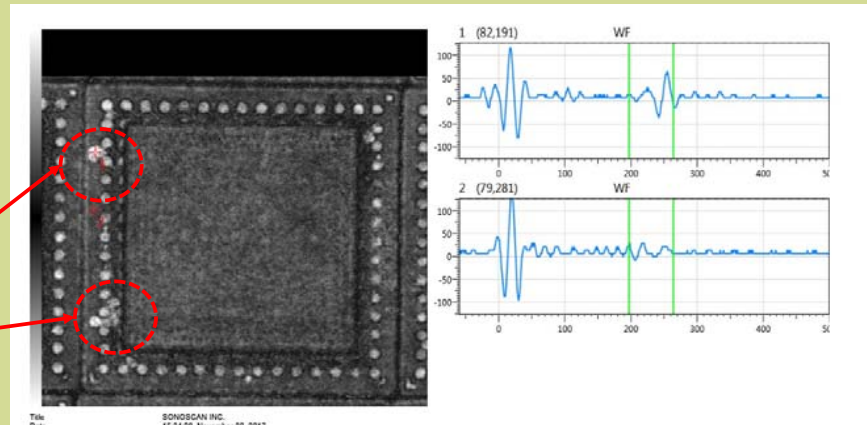
1st Run Reliability Test

Based on eWLB fan out packaging, daisychain dies are used for packaging, and reliability assessment is done for Pre-con, Thermal Cycles (TC), HTS and uHAST according to JEDEC requirements. The major results are shown below.

Types of tests	JEDEC standard	conditions	Test points	failures	Failure modes	Root causes
Pre-con test	JESD22-A113	120°C, 24hrs; 30°C/60%RH, 96hrs; 260°C, 3x reflows;	/	29/248	Delamination between PI	Process and materials
Thermal cycles	JESD22-A104	-40°C~125°C, 10°C/min	320cycles	5/77	-	
			750cycles	59/77	Delamination between PI and dies	Materials
High temperature storage (HTS)	JESD22-A103	150°C, 1008hrs	1008hrs	4/45	EMC filling in and delamination between PI	Process
uHAST	JESD22-A110	130°C, 85%RH, 96hrs	96hrs	5/77	-	
			144hrs	22/77	VOIDS and delamination between solder ball and UBM	Process

Pre-con Reliability Test

The fourth layer of chip 135, Delamination appears at the edge of PI opening.

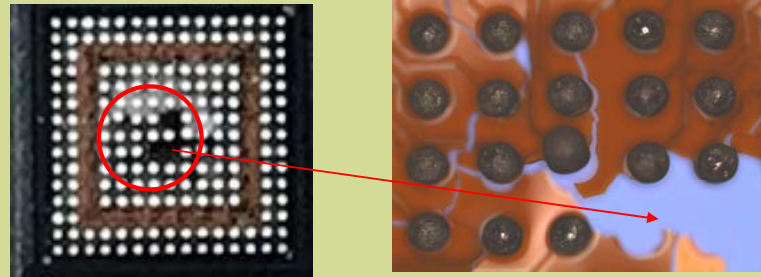


Package Cross Section

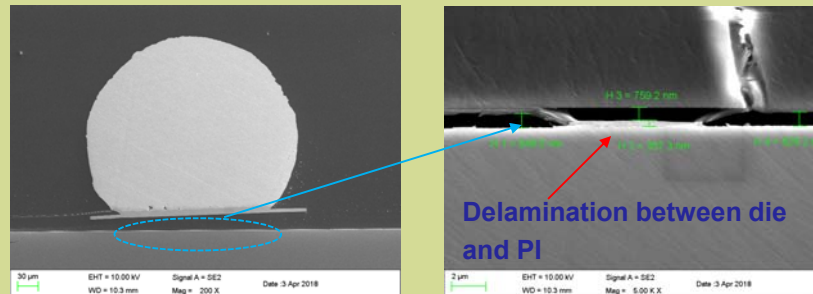
Large Panel Fanout Technology Overview and Development

TC 750 Reliability Test

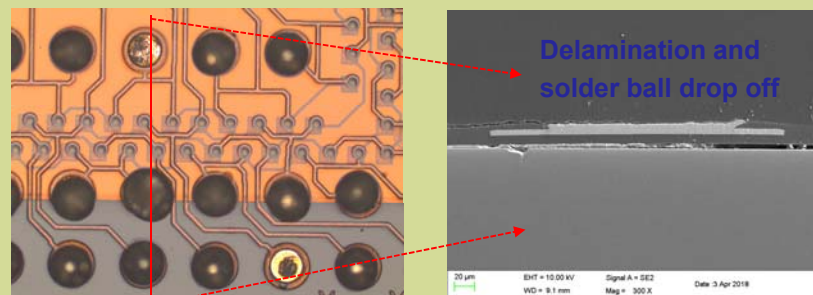
Microscopes showed surface materials drop off from die surface



Cross-section showed delamination occurred between PI and die

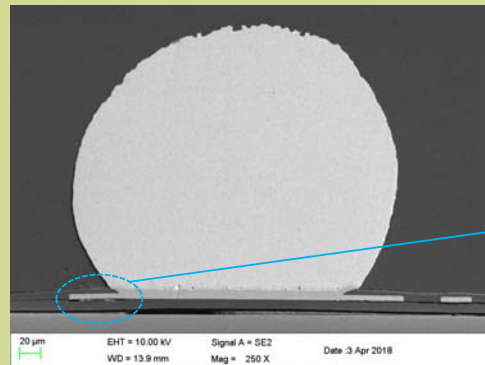
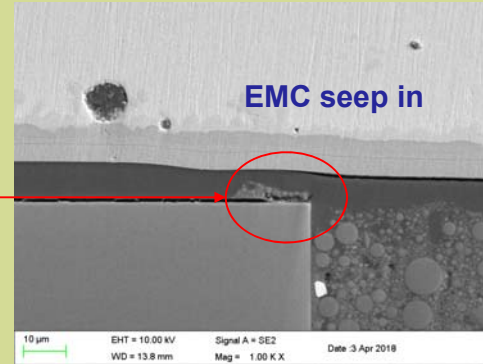
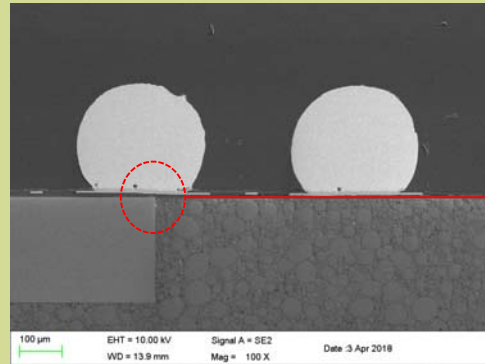


Solder ball drop off



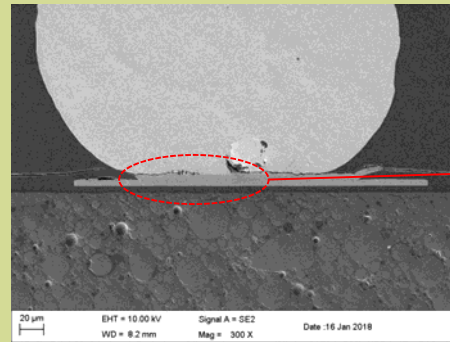
HTS (1000 hrs) Reliability Test

EMC seep into between die and PI interface

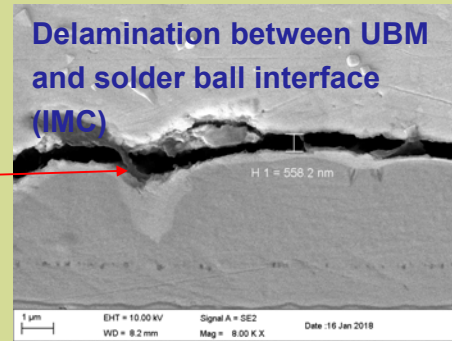


uHAST (144 hrs) Reliability Test

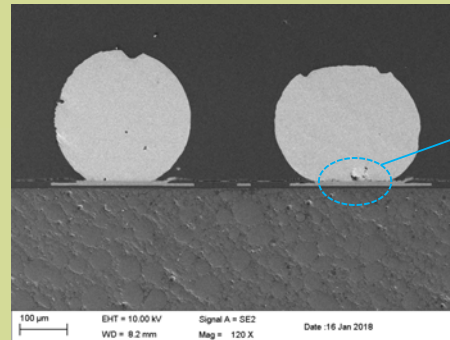
Delamination between UBM and solder ball interface



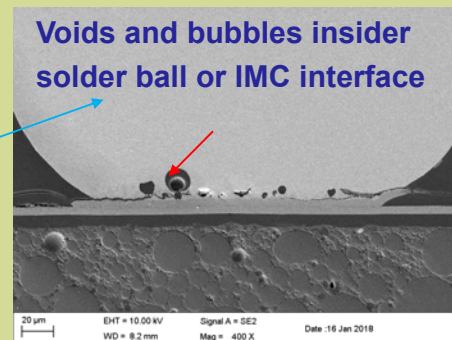
Delamination between UBM and solder ball interface (IMC)



Voids and bubbles occurred at IMC interface



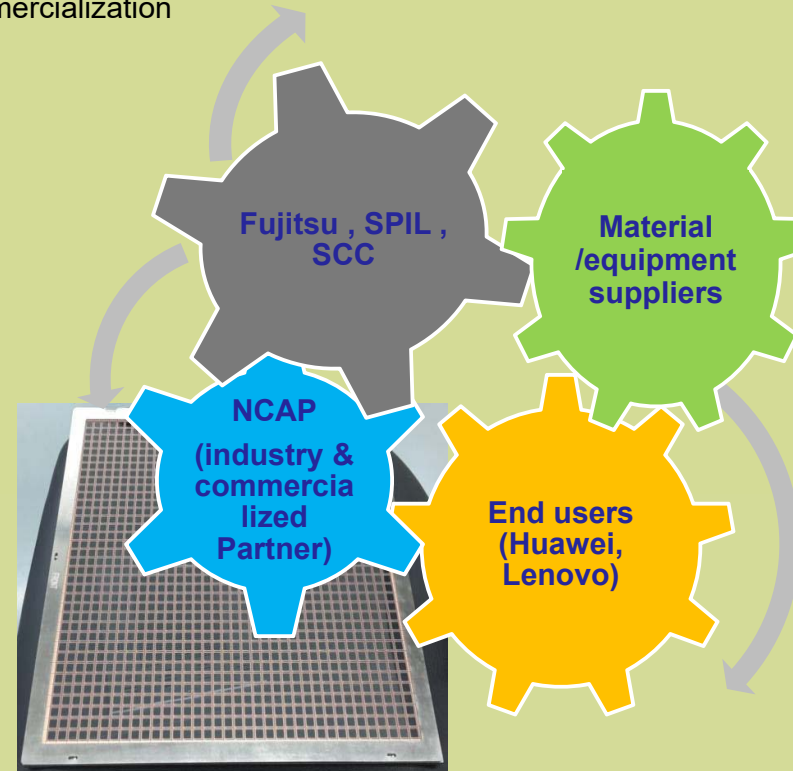
Voids and bubbles insider solder ball or IMC interface



NCAP LPFO Consortium

No.	Key members
1	NCAP
2	SCC (深南)
3	SPIL (Taiwan)
4	Sinopaco (中鹏)
5	AMC (Taiwan)
6	Delphilaser (德龙)
7	Fujitsu
8	TOWA
9	Bee-semi(中电科)
10	JSR
11	Screen
12	KohYoung (高永)
13	Savansys
14	Huawei
15	Mascem (技美)
16	Sumitomo
17	Shin-Etsu(信越)
18	DNP (大日本印刷)
19	ASM
20	Ingenic(君正)
21	ORC
22	SCHOTT
23	Atotech
24	See ray
25	Lenovo

- **Objective:** Development and characterization of large panel fan out design, process and reliability in 2015, provide supply chain analysis and justification for commercialization



Consortium Updates and Complimentary

NCAP has won the "Twelfth (2017) China Semiconductor Innovative Products and Technology" for "Integrated Large Panel Fan-out Advanced Packaging Technology".



Thanks to the supports of all the members of NCAP LPFO Consortium!



2018

Large Panel Fanout Technology Overview and Development

35

Consortium Summary

Consortium

on Low Cost Panel Level Fan-out Technology Development

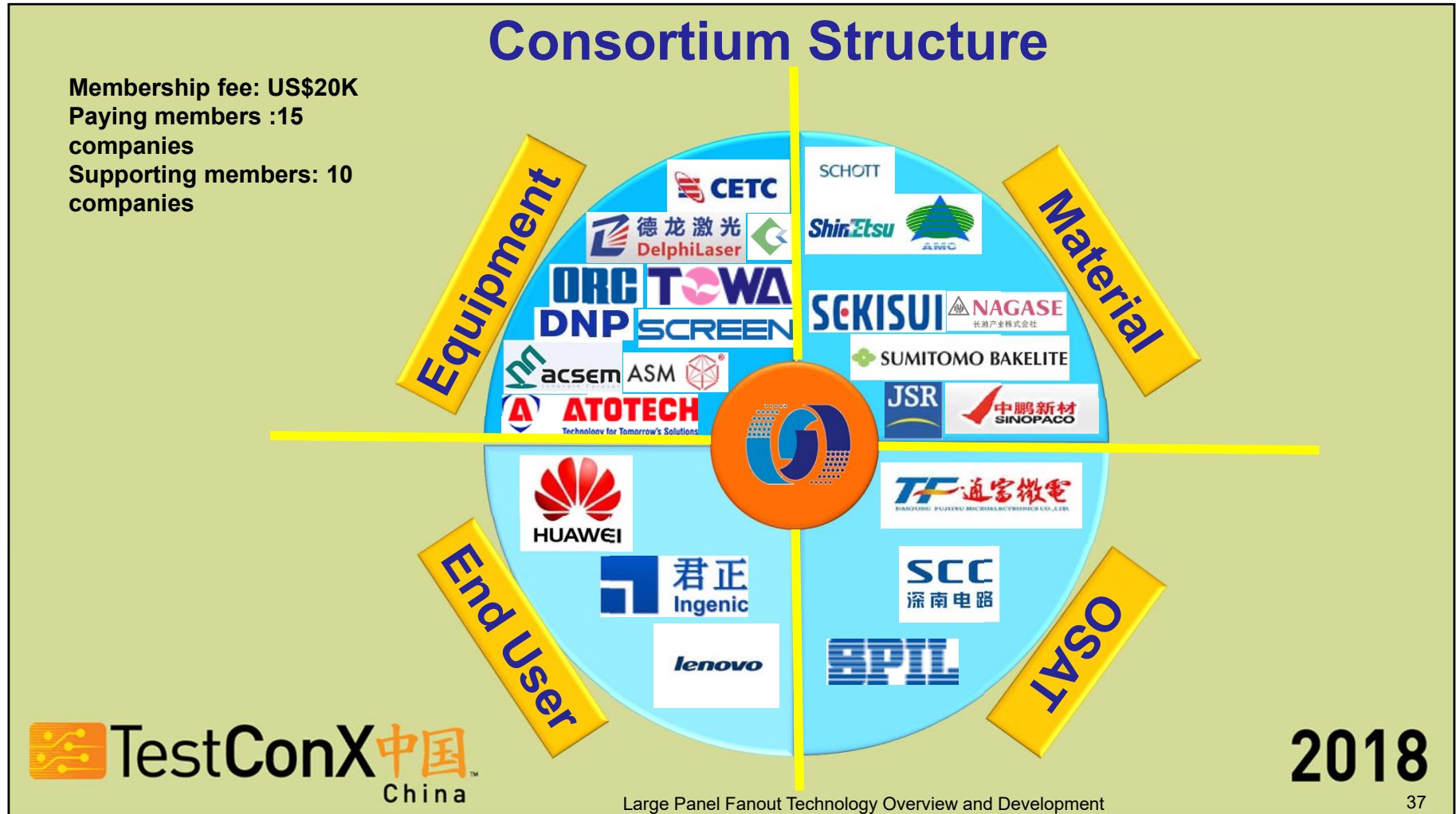
- 25 International Companies joined the Consortium
- Target single die fan-out (one layer RDL) development & demonstration (Phase 1)
- Establish design, simulation, process capability and panel level fan-out supply chain build up
- Complete single die fan-out lesson learnt and preliminary process & reliability qualification
- Drive low cost solutions & commercialization
- Establish panel level fan-out technology Industry chain embryonic in China



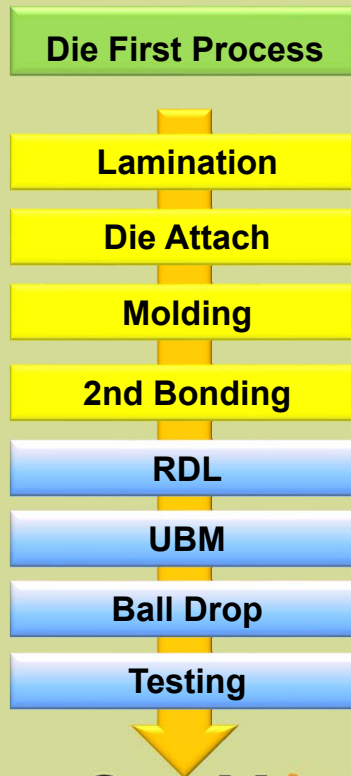
2018

Large Panel Fanout Technology Overview and Development

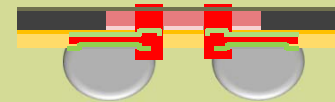
36



Die First Process Characterization



Package structure



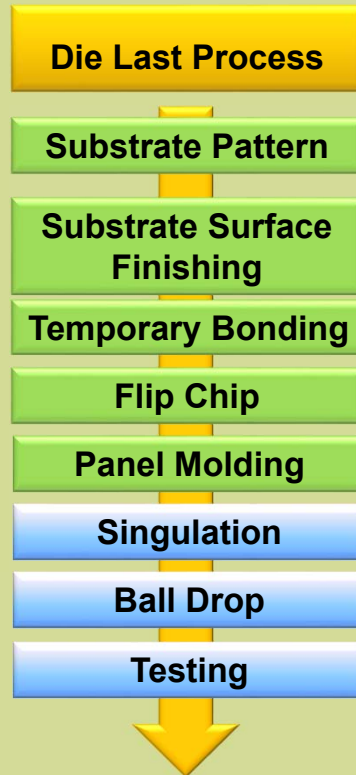
Package size: 8.9 x 7.7 mm
RDL: 1 layer
RDL Line/Space: 20/20 μ m
Ball Pad Size: 250 μ m
Ball Pad PI Open: 230 μ m

Die sizes: 5.24 x 4.835mm
Die pad pitch: 96 μ m
Die thickness: 200 μ m
Die Pad PIO: 65x65 μ m
Die Pad Qty.: 207

Key Benefits

- Have advantage of easier process
- Thinner than flip chip package (no substrate)
- Support increased I/O density
- Excellent electrical and thermal performance
- Excellent high temperature warpage performance
- Fine line & space
- Panel level molding process
- Establishing panel level fan out industrial base

Die Last Process Characterization



Package structure



Package size: 8 x 8 mm
Package ball Qty : 185
Substrate Line: 1 layer
Line/Space: 30/30um

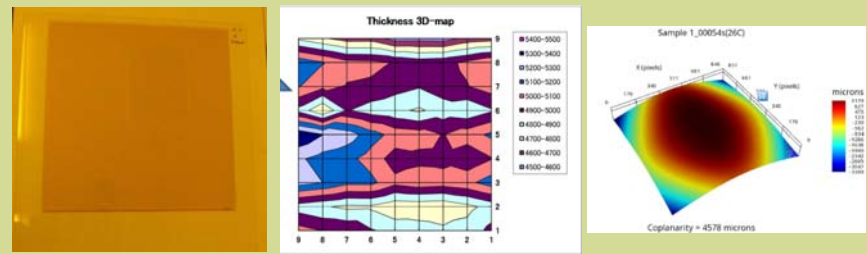
Die sizes: 6 x 6 mm
Die pad pitch: 200 μm
Die Thickness: 150 μm
Cu pillar height : 70um
Copper pillar Qty.: 203

Key Benefits

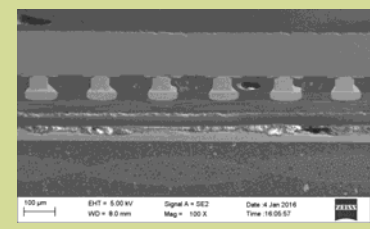
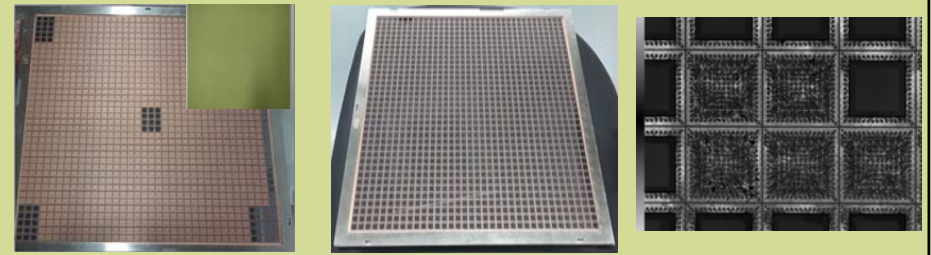
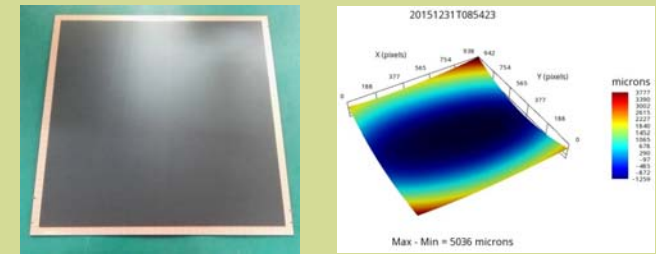
- Utilizes a Low Cost FC Coreless Substrate
- Panel processing (low cost)
- No FO Wafer Fab Investment needed, can use existing Flip Chip Packaging manufacturing lines
- Fan-Out Packages with low thickness
- Design based on flip chip die
- Test as module as usual
- Establishing panel level fan out industrial base

Major Results Sharing

Die First Process



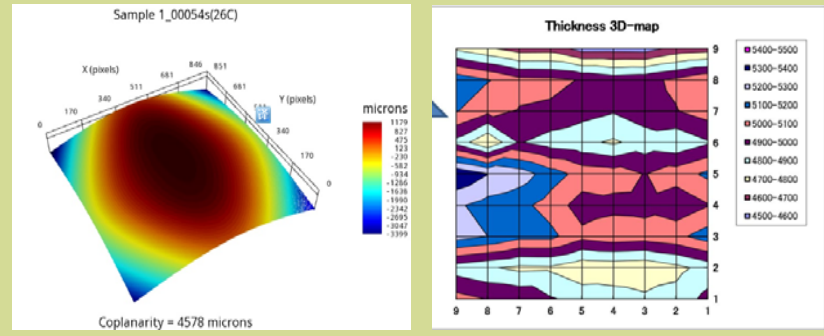
Die Last Process



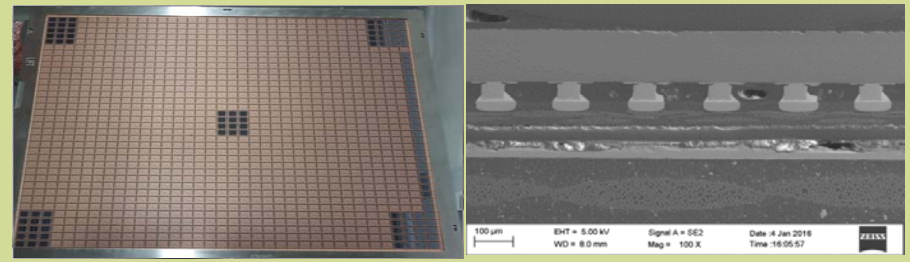
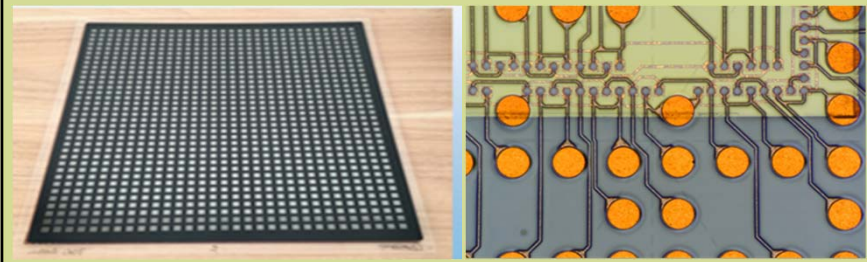
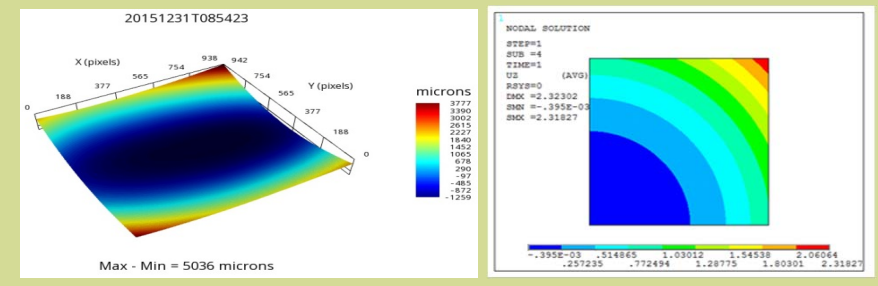
2018

Major Results Sharing

Die First Process



Die Last Process



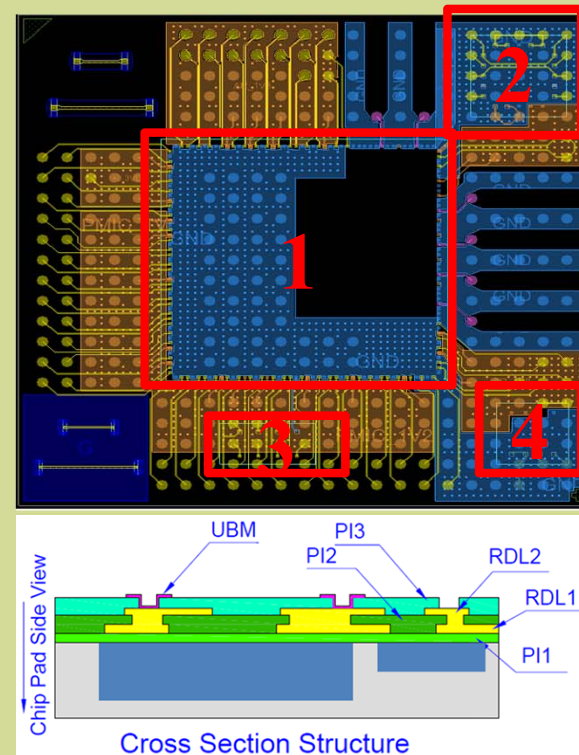
Large Panel Fanout Technology Overview and Development

2018

The Design Of NCAP Phase II FOPLP Consortium

No.	1	2	3	4
Chip Type	MMIC	LDO 02	Flash	LDO 01
Size (mm)	6*6	2*2	2*1	1.5*1.5

- Panel Size: 600mmX600mm
- Package Size: 12mmX12mm
- Min. Line Width/Space: 10um/10um
- Min Chip to Chip Space: 200um
- Integrated Chips Count: 4
- Solder Ball Counts: >300
- RDL Layers: 2 Layers



Future Major Works to Be Done in GD

1. Establishing large panel fan out engineering line and promote domestic equipment capability build up

In the next one year, large panel fan out line will be built up; some critical equipment will be built up, like die bonding, plating, PVD, de-bonding equipment;

2. Equipment and Material Evaluation and Verification

Critical panel level fan out equipment and material will be evaluated and verified;

3. Become partnership with GD semiconductor packaging equipment

- a. Work together and develop new equipment together;
- b. Provide engineering service to important customers;
- c. Provide training centre for universities and institute.

Team Build up in GD

NCAP Team

- Thousand talent program: leaders and experts,
- IP on related fan out know how, consortium experience and relationship;

Guangdong University of Technology team

- Thousand talent program: CQ Cui, with over 20 years of experience
- The National Laboratory of Guangdong University of Technology: research experts, students, etc
- Clean room space

LPFO overseas team

- International team members
- LPFO consortium members and internationally renowned enterprises (equipment, materials suppliers, etc), such as Screen, JSR, Atotech, ASM, TOWA, Sumitomo, SPIL.....

GD local government supports

Conclusions

1. Fan out technologies are commercialized in the major forms of eWLB, RCP, InFO, and other mixed technologies.
2. The market will be booming for fan out especially after Apple iPhone 7 was using InFO technologies. LPFO will be commercialized soon.
3. NCAP has established WLP Fan out and LPFO capability and pass relevant reliability test. LPFO engineering lines will be in GD province.
4. FoZhixin microelectronics Pte Ltd will be a critical window in GD province to show LPFO equipment capability and becoming solution providers.

Acknowledgements

1. Thanks to NCAP 02 National Project supports, which support basic research and commercialized packaging environment build up.
2. Thanks to NCAP LPFO Consortium and provide huge process and reliability assessment, especially thanks to contributions of 25 key members of consortium .
3. Appreciate NCAP senior leadership team and their vision on LPFO.
4. Appreciate GDUT leaders to supports the LPFO engineering lines build up in GD.



Large Panel Fanout Technology Overview and Development

2018

46